



XA-7709G  
PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of:

Kenji NISHI

Appln. No.: 10/721,425

Filed: November 26, 2003

For: PROJECTION EXPOSURE APPARATUS

\* \* \*

SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Sir:

Supplementing the Information Disclosure Statement  
dated November 26, 2003, and without any assertion as to  
materiality or prior art effect, the documents listed on  
the attached Form PTO-1449 are hereby cited.

Respectfully submitted,

NHS:jab

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By: Nelson H. Shapiro  
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Reg. No. 17,095

March 17, 2004

FORM PTO-1449			Atty. Docket No.	Appln. No.
LIST OF DOCUMENTS CITED BY APPLICANT			XA-7709G	10/721,425
			Applicant	
			Kenji NISHI	
			Filing Date	Group
			November 26, 2003	

**U.S. PATENT DOCUMENTS**

Examiner Initial		Document Number	Date	Name	Class	Sub-class	Filing Date
	AA	4,748,478	5/31/88	Suwa et al.	355	53	
	AB	4,829,193	5/9/89	Nishi	250	548	
	AC	4,880,310	11/14/89	Nishi	356	401	
	AD	4,902,900	2/20/90	Kamiya et al.	250	548	
	AE	4,941,093	7/10/90	Marshall et al.	364	413.01	
	AF	4,962,318	10/9/90	Nishi	250	548	
	AG	5,084,729	1/28/92	Yakubo et al.	355	74	
	AH	5,309,198	5/3/94	Nakagawa	355	67	
	AI	5,912,727	6/15/99	Kawai	355	67	
	AJ	RE37,391	9/25/01	Nishi	355	53	

**FOREIGN PATENT DOCUMENTS**

Examiner Initial		Document Number	Date	Country	Class	Sub-class	Translation
	AL	2-65222	3/5/90	Japan			Abstract
	AM	2-116115	4/27/90	Japan			Abstract

**OTHER (including author, title, date, pertinent pages, etc.)**

	AQ	Pfeiffer, H., "Advanced E-Beam System for Manufacturing", SPIE, Vol. 1671, 1992, pp. 100-110.
	AR	Haytcher, E. et al., "Finite Element Analysis of Dynamic Thermal Distortions of an X-ray Mask for Synchrotron Radiation Lithography", SPIE, Vol. 1671, 1992, pp. 347-356.
	AS	Chen, G. et al., "Implementation of Two-State Alignment System into CXrL Aligner", SPIE, Vol. 1671, 1992, pp. 471-486.
	AT	Hohn, F. et al., "Electron Beam Lithography, Directions in Direct Write and Mask Making", SPIE, Vol. 1263, 1990, pp. 152-163.
		Nakayama, Y. et al. "Highly Accurate Calibration Method of Electron-beam Cell Projection Lithography", SPIE, Vol. 1924, 1993, pp. 183-192.
		Franco, E. et al., "What is Required for Collimated Point-Source X-ray Lithography to Achieve an Economically Viable Throughput?", SPIE, Vol. 1924, 1993, pp. 371-380.

Examiner	Date Considered

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.